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Attorney Docket No. 5000.129D Confirmation No. 5148

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Kong et al.

Serial No: 10/685,597

Group Art Unit: 2822

Examiner: Amir Zarabian

Filed: October 16, 2003

For: SINGLE STEP PENDEO-AND LATERAL EPITAXIAL

OVERGROWTH OF GROUP III-NITRIDE EPITAXIAL LAYERS WITH GROUP III-NITRIDE BUFFER LAYER

AND RESULTING STRUCTURES May 11, 2004

Commissioner for Patents Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT CITATION UNDER 37 C.F.R. § 1.97

Dear Sir:

Attached is a list of documents on Form PTO/SB/08A. It is requested that the Examiner consider these documents and officially make them of record in accordance with the provisions of 37 C.F.R. § 1.97 and MPEP § 609.

All references listed, with the exception of U.S. Patent No. 6,153,010, EP 0 942 459 and CN 1258094, were cited by both Applicant and Examiner in related Application No. 10/056,607 filed January 24, 2002, which is a divisional of Serial No. 09/679,799 filed October 5, 2000. We enclose copies of the newly cited foreign documents EP 0 942 459 and CN 1258094. Because the benefit of this application was claimed under 35 U.S.C. 120, no copies of the previously cited documents need to be furnished in accordance with 37 C.F.R. § 198(d); however, copies will be furnished upon request.

Respectfully submitted

Philip Summa Reg. No. 31,573

021176

SUMMA & ALLAN, P.A.

11610 North Community House Road Suite 200, Ballantyne Corporate Park Charlotte, North Carolina 28277-2162

Telephone: 704-945-6700 Facsimile: 704-945-6735

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In re: Kong et al.

Serial No. 10/685,597 Filed: October 16, 2003

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first plass mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

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Substitute for form 1449A/PTO		Complete if Known
	Application Number	10/685,597
INFORMATION DISCLOSURE	Filing Date	October 16, 2003
STATEMENT BY APPLICANT	First Named Inventor	Kong et al.
	Group Art Unit	2812 MAI 1 3 2004 gs.
(use as many sheets as necessary)	Examiner Name	E F
Sheet 1 of 4	Attorney Docket Number	5000.129D

				U.S. PATENT DOCUM	MENTS	
5	Cite	U.S. Patent Doo		Name of Patentee or Applicant	Date of Publication of	Pages, Columns, Lines, Where Relevant
Examiner Initials *	No.1	Number Kind (if kno	Code² own)	of Cited Document	Cited Document MM-DD-YYYY	Passages or Relevant Figures Appear
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Examiner	Cite	Fore	eign Patent Doc	ument	Name of Patentee	Date of Publication of	Pages, Columns, Lines, Where Relevant	
Initials*	No.1	Office ³	Number ⁴	Kind Code ⁵ (<i>if known</i>)	or Applicant of Cited Document	Cited Document MM-DD-YYYY	Passages or Relevant Figures Appear	T ₆
	10	wo	99/18617		Cree Research, Inc.	04-15-1999		
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	18	Japan	9-093315		Nichia Chemical Industries, Inc.	04-11-1997		×

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¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark hee if English language Translation is attached.

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STATEMENT BY APPLICANT Group Art Unit 2812 (use as many sheets as necessary) **Examiner Name** 5000.129D Sheet of Attorney Docket Number

	U.S. PATENT DOCUMENTS								
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				FOREIGI	N PATENT DOCU	MENTS		
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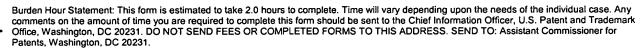
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			CLOSURE	Filing Date	October 16, 2	083
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(use as many sheets as necessary)				Examiner Name		[3 4]
Sheet	3	of	4	Attorney Docket Number	5000.129D	Carried J.

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
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		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²
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